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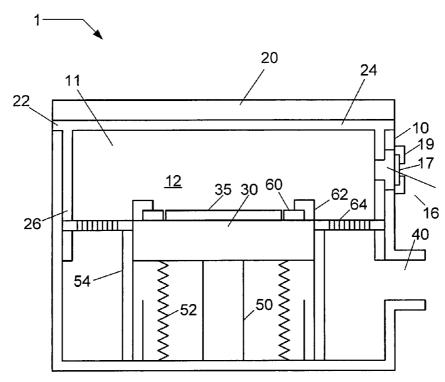
- (71) Applicant: TOKYO ELECTRON LIMITED [JP/JP]; TBS Broadcast Center, 3-6, Akasaka 5-chome, Minato-ku, Tokyo 107-8481 (JP).
- (72) Inventors: NISHIMOTO, Shinya; c/o Tokyo Electron AT Limited, 2381-1, Kitagejo, Fujii-cho, Nirasaki-shi, Yamanashi 407-8511 (JP). MITSUHASHI, Kouji; c/o TOKYO ELECTRON AT LIMITED, 2381-1,

Kitagejo, Fuji-cho, Nirasaki-shi, Yamanashi 407-8511 (JP). NAKAYAMA, Hiroyuki; c/o Tokyo Electron AT Limited, 2381-1, Kitagejo, Fujii-cho, Nirasaki-shi, Yamanashi 407-8511 (JP).

- (74) Agent: SUZUYE, Takehiko; Suzuye & Suzuye, 7-2, Kasumigaseki 3-chome, Chiyoda-ku, Tokyo 100 (JP).
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[Continued on next page]

(54) Title: BAFFLE PLATE IN A PLASMA PROCESSING SYSTEM



(57) Abstract: The present invention presents an improved baffle plate for plasma processing system, wherein the design and fabrication of the baffle plate advantageously provides for a uniform processing plasma in the process space with substantially minimal erosion of the baffle plate.

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Lamo unu I	European Patent Office, P.B. 5818 Patentlaan 2 NL – 2280 HV Rijswijk Tel. (+31–70) 340–2040, Tx. 31 651 epo nl, Fax: (+31–70) 340–3016		Schaub, G		

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